

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Fee only

Application Serial No.10/655,997
Filing Date September 5, 2003
Confirmation No. 7524
Inventor Jon P. Daley
Assignee Micron Technology, Inc.
Group Art Unit 2822
Examiner Pamela E. Perkins
Attorney's Docket No. MI22-2380
Customer No. 021567
Title: Methods of Forming Patterned Photoresist Layers Over Semiconductor
Substrates

RESPONSE TO MARCH 11, 2005 OFFICE ACTION

To: Mail Stop Amendment
Commissioner for Patents
P. O. Box 1450
Alexandria, VA 22313-1450

VIA U.S. EXPRESS MAIL

From: Mark Matkin (Tel. 509-624-4276; Fax 509-838-3424)
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Responsive to the Office Action dated March 11, 2005, Applicant
amends and remarks as follows:

AMENDMENTS

06/13/2005 DBROWN 00000001 230925 10655997
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Thereby, the opposite of what Applicant claims, namely increased footing, occurs by the Duval treatment. Therefore, Applicant's independent claims 30 and 53 recite something which is not found within the teachings of Duval, and the anticipation rejection must be withdrawn for this reason. Action to that end is requested.


Applicant's dependent claims should be allowed as depending from allowable base claims, and for their own recited features which are neither shown nor suggested in the cited art. Action to that end is requested.

Respectfully submitted,

Dated: _____

6-2-05

By: _____


Mark S. Matkin
Reg. No. 32,268